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TITLE: ELECTRON BEAM LITHOGRAPHY APPARATUS

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INVENTOR-INFORMATION:

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ABSTRACT:

PURPOSE: To obtain an electron beam lithography apparatus, which can correct the distortion in the optical system of an exposure device, even if the object of the lithography is a mask or a reticle, by storing the correcting values of the masks and reticle in a computer.

CONSTITUTION: Based on the result of the lithography by a light projecting and exposing device, the distortion characteristics in an optical system are found. Then, the required data for the lithography is inputted through a keyboard and stored in a memory device (disc), which is connected to a control computer as job data (203). When the lithography is actually performed, a lithography control program judges the name of the job data for the lithography and the data is read out (207) of the disc. Whether the light lithography object is a mask (b) or a reticle (a) is judged (209). By using the correcting data, which is stored through the keyboard (205) in an area in a computer, correcting signals suitable for the mask or the reticle are formed (216)(212) and added to the lithography signals having the inherent design values (217)(213). In the result of the lithography, a pattern, in which the

distortion of an optical lens is excellently corrected, is obtained for both the mask and the reticle.

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